

IN THE CLAIMS

1. (Currently Amended) An electron beam apparatus, comprising:

an electron source including an electron-emitting device;

an electron beam irradiation member which is opposed to the electron source and irradiated with an electron emitted from the electron-emitting device;

a potential specifying plate which is located between the electron source and the electron beam irradiation member and which includes a plurality of openings through which the electron emitted from the electron-emitting device transmits; and

a spacer located between the electron beam irradiation member and the potential specifying plate,

wherein ~~in~~ D1 defined as a distance between a region between one opening of the plurality of openings portion of the potential specifying plate between one opening of the plurality of openings of the potential specifying plate, [[which is]] near the spacer and the spacer and the electron beam irradiation member, ~~is D1~~ and D2 defined as a distance between a region a portion of the potential specifying plate between the one opening of the potential specifying plate [[which is]] near the spacer and another opening of the plurality of openings of the potential specifying plate [[which is]] not near the spacer and the electron beam irradiation member, meet is D2; a relationship $D1 < D2$ [[is satisfied]].

2. (Currently Amended) An electron beam apparatus, comprising:

an electron source including an electron-emitting device;
an electron beam irradiation member which is opposed to the electron source and irradiated with an electron emitted from the electron-emitting device;
a potential specifying plate which is located between the electron source and the electron beam irradiation member and which includes a plurality of openings through which the electron emitted from the electron-emitting device transmits; and
a spacer located between the electron source and the potential specifying plate,

wherein ~~in D3 defined as a distance between a region between one opening of the plurality of openings~~ portion of the potential specifying plate between one opening of the plurality of openings of the potential specifying plate, [[which is]] near the spacer and the spacer and the electron-emitting device, ~~by D3 and D4 defined as a distance between a region between the one opening~~ portion of the potential specifying plate between the one opening of the potential specifying plate [[which is]] near the spacer and another opening of the plurality of openings of the potential specifying plate [[which is]] not near the spacer and the electron-emitting device, meet ~~is D4~~, a relationship $D3 > D4$ [[is satisfied]].

3. (Currently Amended) An electron beam apparatus according to claim 1, wherein a thickness of the ~~region between the one opening~~ portion of the potential specifying plate between the one opening of the potential specifying plate [[which is]] near

the spacer and the spacer is larger than a thickness of ~~another region~~ the portion of the potential specifying plate between the one opening of the potential specifying plate near the spacer and another opening of the plurality of openings of the potential specifying plate, not near the spacer.

4. (Currently Amended) An electron beam apparatus according to claim 2, wherein a thickness of the ~~region between the one opening~~ portion of the potential specifying plate [[which is]] near [[to]] the spacer and the another opening of the potential specifying plate [[which is]] not near the spacer is larger than a thickness of ~~another region~~ the portion of the potential specifying plate between the one opening of the plurality of openings of the potential specifying plate near the spacer and the spacer.

5. (Original) An electron beam apparatus according to claim 1, wherein the potential specifying plate has, between the one opening near the spacer and the spacer, a protrusion protruding toward a side of the electron beam irradiation member.

6. (Original) An electron beam apparatus according to claim 2, wherein the potential specifying plate has, between the opening near the spacer and the another opening not near the spacer, a protrusion protruding toward a side of the electron beam irradiation member.